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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 08/696,243  
Priority Filing Date 08/13/96  
Inventor Schuegraf  
Assignee Micron Technology, Inc.  
Priority Group Art Unit 2813  
Priority Examiner M. Whipple  
Attorney's Docket No. MI22-1098  
Title: Semiconductor Processing Methods of Chemical Vapor Depositing SiO<sub>2</sub> on  
a Substrate

PRELIMINARY AMENDMENT

To: Box PATENT APPLICATION  
Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Lance R. Sadler (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
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Sir:

Applicant preliminarily amends as follows:

AMENDMENTS

In the Specification

On page 1, before the "Technical Field" section, insert the  
following section:

--RELATED PATENT DATA

This patent resulted from a continuation application of U.S. Patent  
Application Serial No. 08/696,243, filed August 13, 1996, entitled  
"Semiconductor Processing Methods of Chemical Vapor Depositing SiO<sub>2</sub>